

## IN THE SPECIFICATION

Please replace the paragraph beginning on page 9, line 13 and ending on page 10, line 5 with the following paragraph:

-- FIGs. 2A and 2B illustrate an example of an SLM 110 with liquid crystal (LC) light modulation elements 210 that define pixels of an image. The SLM 110 in FIGs. 2A and 2B is a liquid crystal on silicon (LCOS) SLM [[100]] including individual LC light modulation elements 210 that selectively reflect light of a particular polarization to transfer an image of a pattern onto a substrate. FIG. 2A is an exploded view of a portion of the LCOS SLM, and FIG. 2B is a cross-sectional view of an LC light modulation element 210 of the LCOS SLM 110. As can be seen in FIG. 2A, the LCOS SLM 110 includes a substrate 200 on which pixel electrodes 215 are located. The pixel electrodes 215 can be arranged in an array of rows and columns or in a nonorthogonal pattern. Within the substrate 200 below each pixel electrode 215 is located a pixel drive circuit 250 connected to drive the overlying pixel electrode 215. Disposed above the substrate 200 is a transparent glass 230 coated with a layer 235 of transparent electrically conductive material, such as indium tin oxide (ITO). The ITO layer 235 is the common electrode of the LCOS SLM 110. Encapsulated between the substrate 200 and the glass 230 is a layer 220 of liquid crystal material that reacts in response to electric fields established between the common electrode 235 and pixel electrodes 215. --

Please replace the paragraph beginning on page 13, line 13 and ending on page 14, line 4 with the following paragraph:

-- In FIG. 5, a portion of rendering 400b is shown spatially selected after a portion of rendering 400a along the x-axis to shift a starting point 415 of resized pattern 510 to the ~~[[left]]~~ right  $\frac{1}{2}$  of a pixel from the start of pattern 410 in rendering 400a. In addition, a portion of rendering 400a is shown spatially selected after rendering 400b along the x-axis to shift an ending point 420 of resized pattern 510 to the right  $\frac{1}{2}$  of a pixel from the end of pattern 410 in rendering 400b. The result of the combination of renderings 400a and 400b in FIG. 5 is a rendering 500 of a resized pattern 510 that has been stretched approximately 5% in the x-direction. It should be understood that the number and size of selected portions of each available rendering varies along both the x-axis and the y-axis to accommodate any alignment, size or other type of distortion. By selecting portions of spatially offset renderings to resize a pattern, the average error for an offset of  $\frac{1}{2}$  of a light modulation element is only  $\frac{1}{8}$  light modulation element, and the peak error is only  $\frac{1}{4}$  light modulation element. In addition, pattern and image resizing can be performed in real time to compensate for distortions in the substrate surface or optics, while maintaining high throughput rates. --